1. Title:	Current Status of EULV mask blank coating development in AGC
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3. Abstract body:

Recent rapid progress in EUVL technology is ensuring that EUVL will be a primary candidate for the next generation lithography beyond 32-nm node. However, realization of defect-free mask blank is still counted as one of the most critical issues for high volume production in EUVL. AGC has developed comprehensive technologies for manufacturing an EUVL mask blank from Low Thermal Expantion Material (LTEM) to polishing glass substrate, surface cleaning, multilayer coating, and evaluating its performances by making use of our long and wide experience in providing high quality processed glass substrate and coating for electronic devices. In this paper, we will present the current status of EUVL mask blank coating development in AGC toward the specifications required for high volume production.